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STRUCTURE FILE UPDATES: 10 MAR 2009 HIGHEST RN 1118786-80-3 DICTIONARY FILE UPDATES: 10 MAR 2009 HIGHEST RN 1118786-80-3

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http://www.cas.org/support/stngen/stndoc/properties.html

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L7 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2009 ACS on STN

RN 866568-62-9 REGISTRY

ED Entered STN: 02 Nov 2005

CN 2-Propenoic acid, 2-methyl-, [[[2-(phenylazo)ethoxy]carbonyl]oxy]methyl ester, homopolymer (9CI) (CA INDEX NAME)

MF (C14 H16 N2 O5) x

CI PMS

PCT Polyacrylic

SR CA

LC STN Files: CA, CAPLUS, USPATFULL

CM 1

CRN 866568-61-8 CMF C14 H16 N2 O5

$$\stackrel{\text{H2C}}{\underset{\text{Me}}{\square}} \stackrel{\text{O}}{\underset{\text{C}}{\square}} = \stackrel{\text{O}}{\underset{\text{C}}} = \stackrel{\text{O}}{\underset{\text{C}}} = \stackrel{\text{O}}{\underset{\text{C}}} = \stackrel{\text{O}}{\underset{\text{C}}} = \stackrel{\text{O}}{\underset{\text{C}}} = \stackrel{\text{O}}{\underset{C$$

1 REFERENCES IN FILE CA (1907 TO DATE)

1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

REFERENCE 1: 143:396461

L7 ANSWER 2 OF 2 REGISTRY COPYRIGHT 2009 ACS on STN

RN 866568-61-8 REGISTRY

ED Entered STN: 02 Nov 2005

CN 2-Propenoic acid, 2-methyl-, [[[2-(2-

10 / 593884 2

phenyldiazenyl)ethoxy]carbonyl]oxy]methyl ester (CA INDEX NAME)
OTHER CA INDEX NAMES:

CN 2-Propenoic acid, 2-methyl-, [[[2-(phenylazo)ethoxy]carbonyl]oxy]methyl ester (9CI)

MF C14 H16 N2 O5

CI COM

SR CA

$$\begin{array}{c|c} ^{\rm H_2\,C} & \circ & \circ \\ \text{Me-} & C - C - \circ - \text{CH}_2 - \circ - C - \circ - \text{CH}_2 - \text{CH}_2 - \text{N} \underline{\qquad} \text{N-Ph} \\ \end{array}$$

PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

=> fil hcaplus
FILE 'HCAPLUS' ENTERED AT 06:23:04 ON 12 MAR 2009
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FILE COVERS 1907 - 12 Mar 2009 VOL 150 ISS 11 FILE LAST UPDATED: 11 Mar 2009 (20090311/ED)

HCAplus now includes complete International Patent Classification (IPC) reclassification data for the third quarter of 2008.

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This file contains CAS Registry Numbers for easy and accurate substance identification.

=> d 19 bib abs hitstr

- L9 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2009 ACS on STN
- AN 2005:1106945 HCAPLUS Full-text
- DN 143:396461
- TI Micropattern phase difference element
- IN Matsunaga, Daisaku; Hashimoto, Masanori; Ruslim, Christian; Tamaki, Takashi; Ichimura, Kunihiro
- PA National Institute of Advanced Industrial Science and Technology, Japan; Nippon Kayaku Kabushiki Kaisha
- SO PCT Int. Appl., 39 pp.

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CODEN: PIXXD2

DT Patent

LA Japanese

FAN.CNT 1

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PATENT NO.
                      KIND DATE
                                       APPLICATION NO.
                                                             DATE
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                       A1 20051013 WO 2005-JP5848
PΙ
    WO 2005096041
                                                              20050329 <--
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            CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
            GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
            LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
            NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM,
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        RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
            AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
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            RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML,
            MR, NE, SN, TD, TG
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    US 20070134442 A1
                                                              20060921 <--
                       Α
                              20040330 <--
PRAI JP 2004-99122
                       A 20040330 <--
W 20050329 <--
    WO 2005-JP5848
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The invention is concerned about a micropattern phase difference element requiring no stretch processing and an extremely high positioning accuracy such as in cutting a film, and controlling the phase difference region with a width of micron unit and its producing method. The micropattern phase difference element can be obtained by providing a liquid crystal or non-liquid crystal polymer thin film layer having photoactive groups on a substrate, performing orientation in a micropattern from, and then providing a double refraction layer in contact with the polymer thin film layer, thereby orienting double refraction mols. in the double refraction layer according to orientation of photoactive groups in the thin film. The phase difference element is used in a three-dimensional display, or the like.

IT 866568-62-9

RL: DEV (Device component use); USES (Uses) (micropattern phase difference element)

RN 866568-62-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, [[[2-(phenylazo)ethoxy]carbonyl]oxy]methyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 866568-61-8 CMF C14 H16 N2 O5

$$\begin{array}{c|c} ^{\rm H_2\,C} \\ \text{Me} \\ -\text{C} \\ -\text{C} \\ -\text{O} \\ -\text{CH}_2 \\ -\text{O} \\ -\text{CH}_2 \\ -\text{CH}_2 \\ -\text{CH}_2 \\ -\text{N} \\ \end{array} \begin{array}{c} \text{N} \\ \text{N} \\ -\text{Ph} \\ \end{array}$$

RE.CNT 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

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(FILE 'HOME' ENTERED AT 06:18:43 ON 12 MAR 2009) SET COST OFF

FILE 'HCAPLUS' ENTERED AT 06:19:00 ON 12 MAR 2009

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L1 L2		2 S US200 70134442/PN OR (US2006-593884# OR JP2004-99122 OR WO200 1 S L1 NOT CHEN?/AU SEL RN
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L8 L9	FILE	'HCAPLUS' ENTERED AT 06:21:37 ON 12 MAR 2009 1 S L7 1 S L2,L8
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